

Structural, Optical and Photoelectrochemical Characterizations of Monoclinic Ta₃N₅ Thin Films

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†Supplementary Information

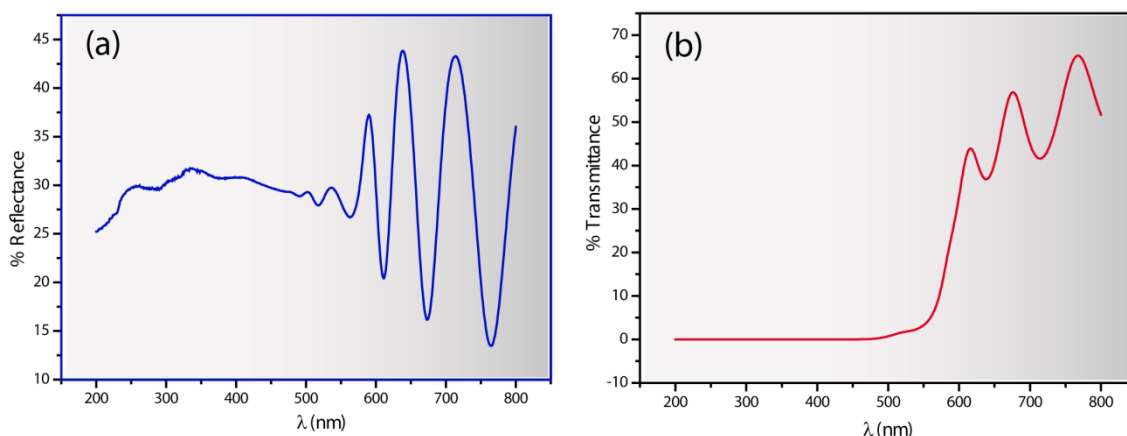


Fig. S1 UV-Vis (a) Reflectance and (b) Transmittance spectra of Ta₃N₅ thin films.

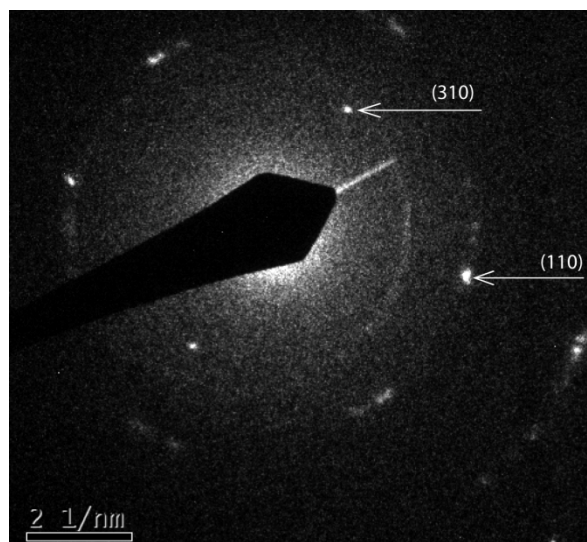


Fig. S2 SAED pattern of monoclinic Ta_3N_5 thin film.

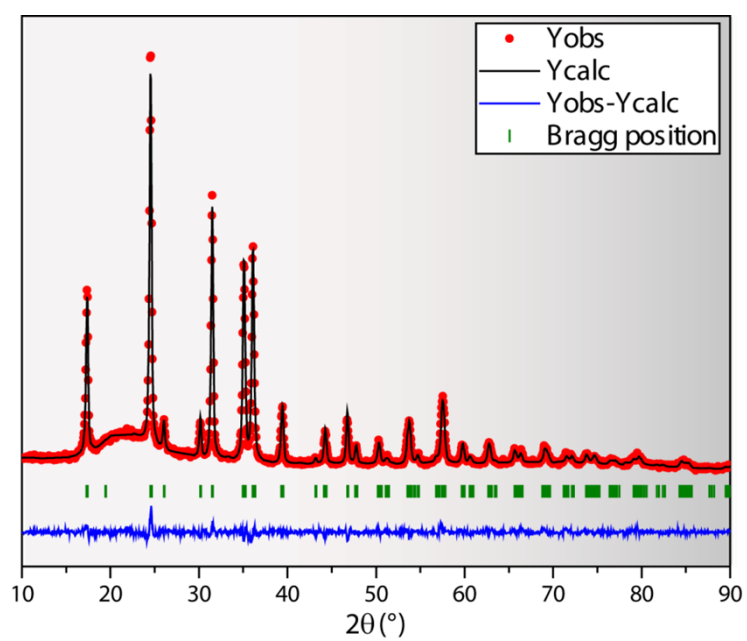


Fig. S3 Rietveld refinement fitting curves.

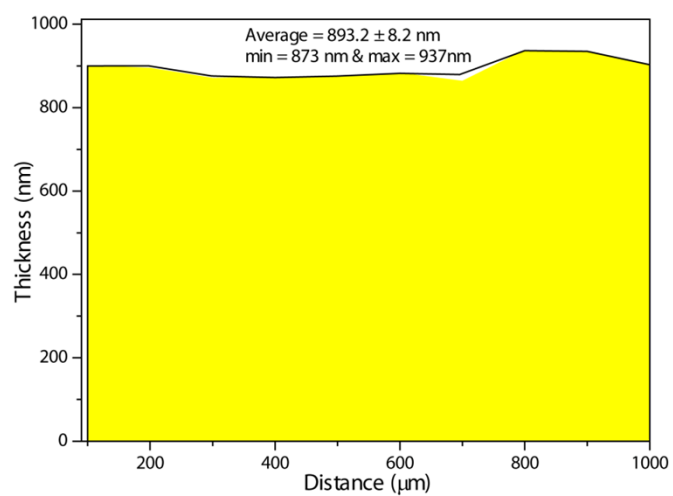


Fig. S4 Profilometry of Ta_3N_5 thin film.

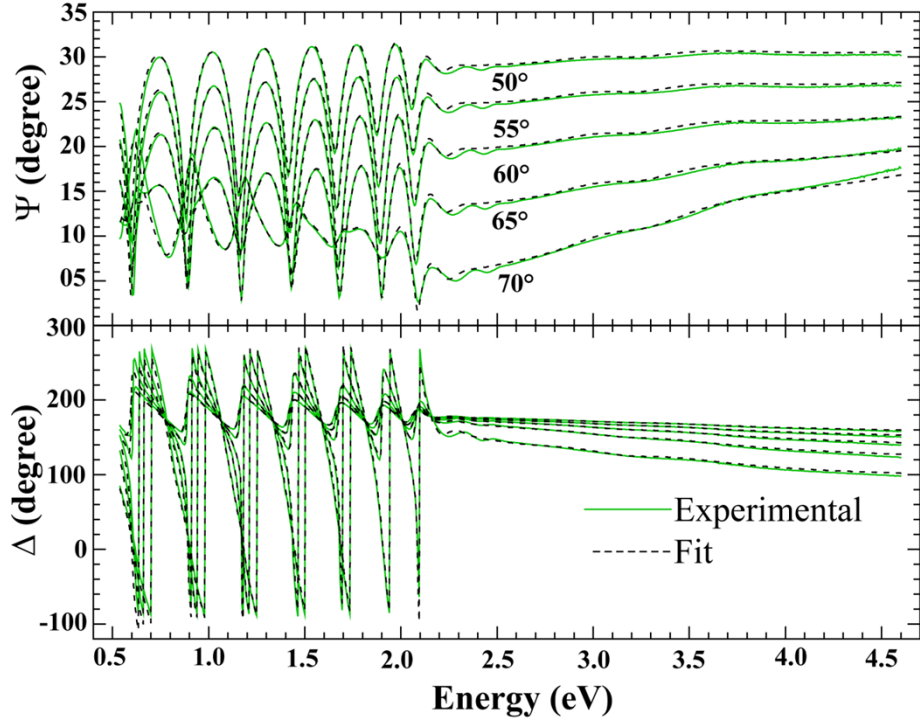


Fig. S5 The experimental SE parameters Ψ and Δ (green lines) fitted by the model (black dashed lines).

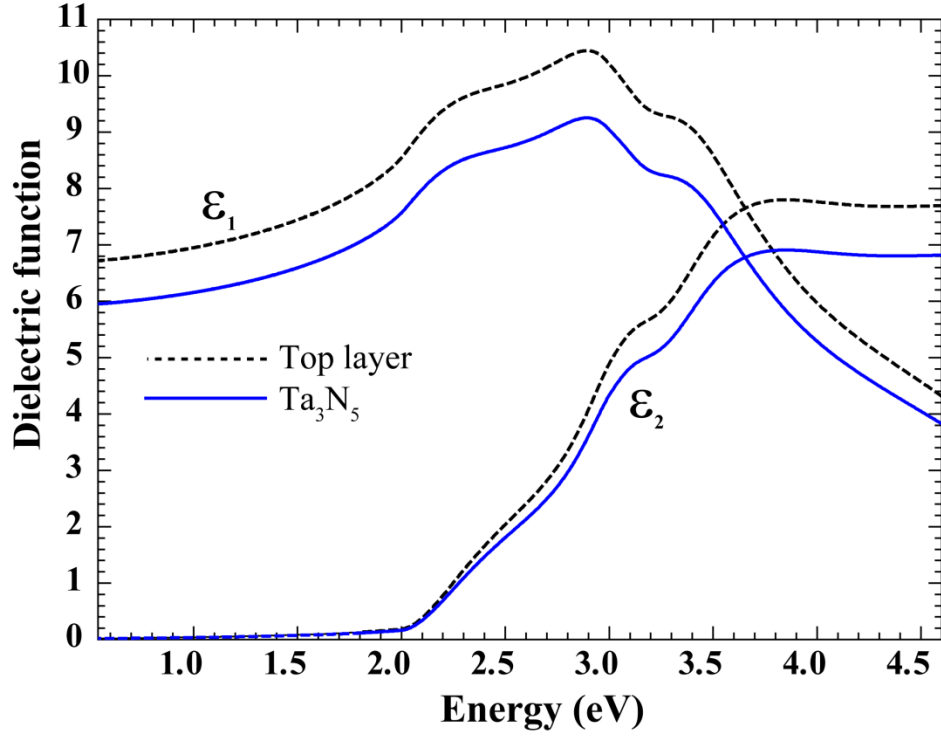


Fig. S6 Real ϵ_1 and imaginary ϵ_2 parts of dielectric functions for top layer and sub-top layer obtained by the SE analyses.

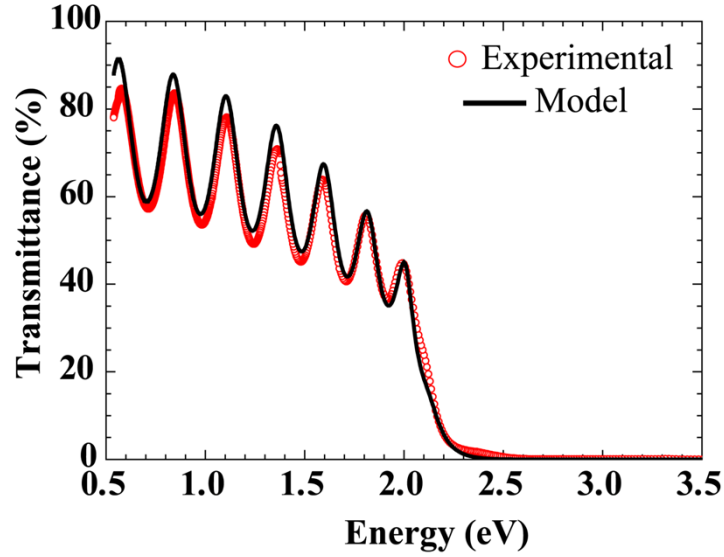


Fig. S7 Transmittance of the Ta_3N_5 films calculated from the parameterization of the SE data (black line) and experimentally measured by the UV-Vis-NIR spectroscopy (red circles).

Table. S1 The bond distances ($\text{\AA}$), average grain size and grain size as a function of (hkl) (nm) obtained from Rietveld refinement.

Average	Bond distances ($\text{\AA}$)				
	Size (nm)				
	h00	0k0	00l	hk0	0kl
40.428	38.215	38.193	44.725	38.196	38.906

Table. S2 The atomic sites and their %occupancies and %vacancies obtained by Rietveld refinement of Ta_3N_5 *

Atom	Wyckoff Position	x	y	z	Site occupancy (%)	Site vacancy (%)
Ta1	4i	0.18857	0.00000	0.25000	99.18	0.82
Ta2	4i	0.13462	0.00000	0.56330	100.00	0.00
Ta3	4i	0.12534	0.00000	0.93594	100.00	0.00
N1	4i	0.75000	0.00000	0.25000	96.95	3.05
N2	4i	0.09349	0.00000	0.06327	98.72	0.00
O1		0.03693	0.00000	0.15532	1.28	
N3	4i	0.07089	0.00000	0.38304	90.95	0.00
O2		0.03287	0.00000	0.38067	9.05	
N4	4i	0.31792	0.00000	0.04001	100.00	0.00
N5	4i	0.30020	0.00000	0.42430	100.00	0.00

*Space group, $C 2/m$, $a=10.2058\text{\AA}$; $b=3.8863\text{\AA}$, $c=10.2636\text{\AA}$, $\alpha=\beta=\gamma=90^\circ$
 $R_p=3.04$; $R_{Bragg}=3.10$, $\chi^2=1.61$.